Applicant
 : Isamu Kobori, et al.
 Attorney's Docket No.: 07977 

 Serial No.: 10/713.275
 024004 / US2975D1D1D1

Filed : November 17, 2003

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## Amendments to the Claims

This listing of claims replaces all prior versions and listings of claims in the application.

## Listing of Claims

1-15. (Canceled)

16. (Currently Amended) An active matrix A circuit comprising:

a transistor comprising a plurality of semiconductor islands;

a semiconductor layer;

a p-type impurity region provided in said-semiconductor-layer each of said semiconductor islands;

a first interlayer insulating film comprising silicon nitride provided over said semiconductor layer semiconductor islands;

a conductive layer comprising titanium and aluminum over said first interlayer insulating film; and

a second interlayer insulating film provided over said conductive layer to provide a leveled upper surface over said semiconductor layer islands.

wherein said titanium and said aluminum are formed in a multi-layer film wherein each of said semiconductor islands has a planar area of  $1000~\mu m^2$  or less.

- 17. (Currently Amended) A circuit according to claim 16 wherein said aetive matrix circuit is incorporated into a liquid-crystal display.
- 18. (Currently Amended) A circuit according to claim 16 wherein said active matrix circuit is incorporated into an image sensor.
- (Currently Amended) A circuit according to claim 16 wherein said active matrix circuit is incorporated into a liquid-crystal electro-optical device.

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(Currently Amended) A circuit according to claim 16 wherein said semiconductor layer each of said semiconductor islands comprises a crystal silicon.

21. (Currently Amended) An active matrix circuit comprising: <u>a transistor comprising a plurality of semiconductor islands and provided in a pixel;</u> <u>a semiconductor layer;</u>

a p-type impurity region provided in said-semiconductor-layer each of said semiconductor islands;

a first interlayer insulating film comprising a silicon nitride layer and a silicon oxide layer, said first interlayer insulating film provided over said semiconductor layer islands;

a conductive layer comprising titanium and aluminum over said first interlayer insulating film; and

a second interlayer insulating film provided over said conductive layer to provide a leveled upper surface over said semiconductor layer islands; and

a pixel electrode provided over said second interlayer insulating film and connected with said p-type impurity region.

wherein each of said semiconductor islands has a planar area of 1000  $\mu m^2$  or less.

- 22. (Previously Presented): A circuit according to claim 21 wherein said active matrix circuit is incorporated into a liquid-crystal display.
- 23. (Previously Presented): A circuit according to claim 21 wherein said active matrix circuit is incorporated into an image sensor.
- 24. (Previously Presented): A circuit according to claim 21 wherein said active matrix circuit is incorporated into a liquid-crystal electro-optical device.

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 (Currently Amended) A circuit according to claim 21 wherein said-semiconductor layer each of said semiconductor islands comprises a crystal silicon.

26. (Currently Amended) An active matrix A drive circuit comprising: at least one transistor comprising a plurality of semiconductor islands; a semiconductor layer:

a p-type impurity region provided in said-semiconductor-layer each of said semiconductor islands:

a first interlayer insulating film comprising silicon nitride provided over said semiconductor layer islands;

a conductive layer comprising titanium and aluminum over said first interlayer insulating film; and

a second interlayer insulating film provided over said conductive layer to provide a leveled upper surface over said semiconductor <del>layer</del> <u>islands</u>, <u>and</u>

wherein each of said semiconductor islands has a planar area of 1000  $\mu$ m<sup>2</sup> or less.

- (Previously Presented): A circuit according to claim 26 wherein said conductive layer comprises an electrode.
- 28. (Previously Presented): A circuit according to claim 26 wherein said conductive layer comprises a wiring.
- (Currently Amended) A circuit according to claim 26 wherein said active matrix drive circuit is incorporated into a liquid-crystal display.
- 30. (Currently Amended) A circuit according to claim 26 wherein said active matrix drive circuit is incorporated into an image sensor.

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31. (Currently Amended) A circuit according to claim 26 wherein said active matrix drive circuit is incorporated into a liquid-crystal electro-optical device.

- 32. (Currently Amended) A circuit according to claim 26 wherein said-semiconductor laver each of said semiconductor islands comprises a crystal silicon.
  - 33. (Canceled).
  - 34. (Currently Amended) An active matrix A circuit comprising:

a transistor comprising a plurality of semiconductor islands;

a semiconductor laver;

- a p-type impurity region provided in said-semiconductor layer each of said semiconductor islands:
- a first interlayer insulating film comprising silicon nitride provided over said semiconductor <del>layer</del> islands;
- a conductive layer comprising titanium and aluminum over said first interlayer insulating film, said conductive layer connected with said p-type impurity region; and
- a second interlayer insulating film provided over said conductive layer to provide a leveled upper surface over said semiconductor layer islands.

wherein said titanium and said aluminum are formed in a multi-layer film. wherein each of said semiconductor islands has a planar area of  $1000 \ \mu m^2$  or less.

- 35. (Currently Amended) A circuit according to claim 34 wherein said aetive matrix circuit is incorporated into a liquid-crystal display.
- (Currently Amended) A circuit according to claim 34 wherein said active matrix circuit is incorporated into an image sensor.

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37. (Currently Amended) A circuit according to claim 34 wherein said-semiconductor layer each of said semiconductor islands comprises a crystal silicon.

38. (Currently Amended) An active matrix circuit comprising:

a transistor comprising a plurality of semiconductor islands;

a semiconductor layer;

a <u>pair of p-type impurity region regions</u> provided in said-semiconductor layer <u>each of said</u> semiconductor islands;

a first interlayer insulating film comprising a silicon nitride layer and a silicon oxide layer, said first interlayer insulating film provided over said semiconductor layer islands;

a conductive layer comprising titanium and aluminum over said first interlayer insulating film, said conductive layer connected with one of said p-type impurity region; and

a second interlayer insulating film provided over said conductive layer to provide a leveled upper surface over said semiconductor layer islands; and

a pixel electrode provided over said second interlayer insulating film and connected with the other of said p-type impurity regions.

wherein each of said semiconductor islands has a planar area of 1000  $\mu m^2$  or less.

- 39. (Previously Presented) A circuit according to claim 38 wherein said active matrix circuit is incorporated into a liquid-crystal display.
- 40. (Previously Presented) A circuit according to claim 38 wherein said active matrix circuit is incorporated into an image sensor.
- (Currently Amended) A circuit according to claim 38 wherein said semiconductor layer each of said semiconductor islands comprises a crystal silicon.
  - 42. (Currently Amended) An active matrix A drive circuit comprising:

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at least one transistor comprising a plurality of semiconductor islands;

a semiconductor layer:

a p-type impurity region provided in said-semiconductor layer each of said semiconductor islands;

a first interlayer insulating film comprising silicon nitride provided over said semiconductor layer islands;

a conductive layer comprising titanium and aluminum over said first interlayer insulating film, said conductive layer connected with said p-type impurity region; and

a second interlayer insulating film provided over said conductive layer to provide a leveled upper surface over said semiconductor layer islands,

wherein each of said semiconductor islands has a planar area of 1000  $\mu$ m<sup>2</sup> or less.

- 43. (Currently Amended) A circuit according to claim 42 wherein said active matrix drive circuit is incorporated into a liquid-crystal display.
- 44. (Currently Amended) A circuit according to claim 42 wherein said active matrix drive circuit is incorporated into an image sensor.
- 45. (Currently Amended) A circuit according to claim 42 wherein said semiconductor layer each of said semiconductor islands comprises a crystal silicon.